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(54) **DEVICE WITH MOLD CAP AND METHOD THEREOF**

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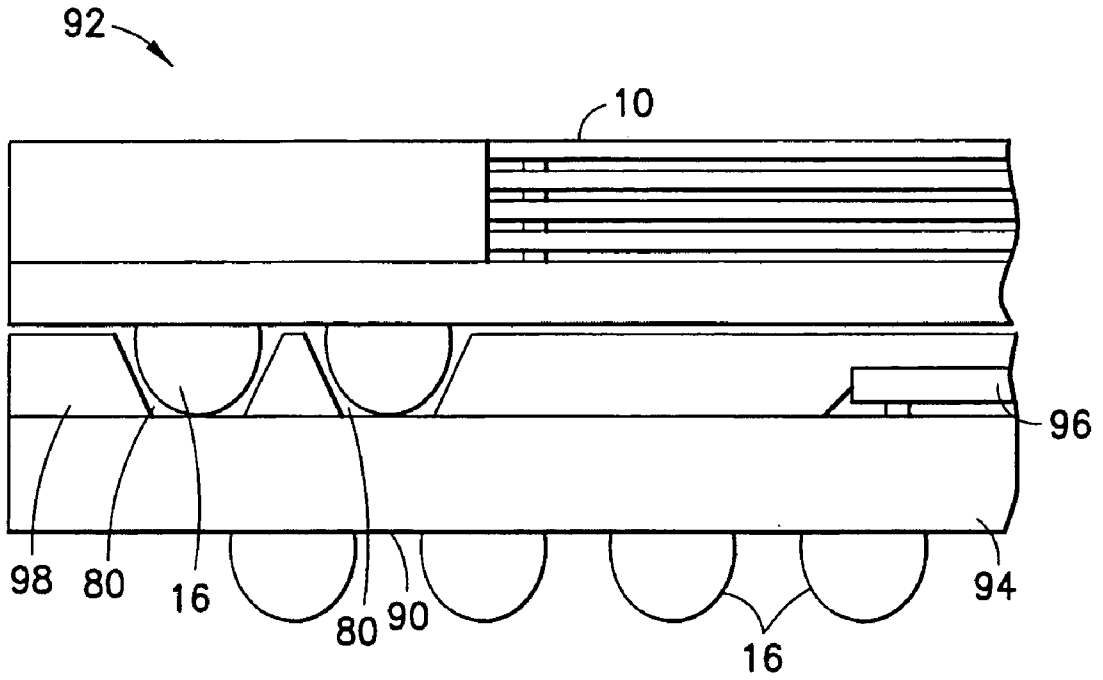
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(57) **ABSTRACT**

A device including a substrate; at least one semiconductor die on a first side of the substrate; and a mold cap molded on portions of the first side of the substrate and on lateral sides of the at least one semiconductor die. The mold cap is not molded onto a top side of the at least one semiconductor die.



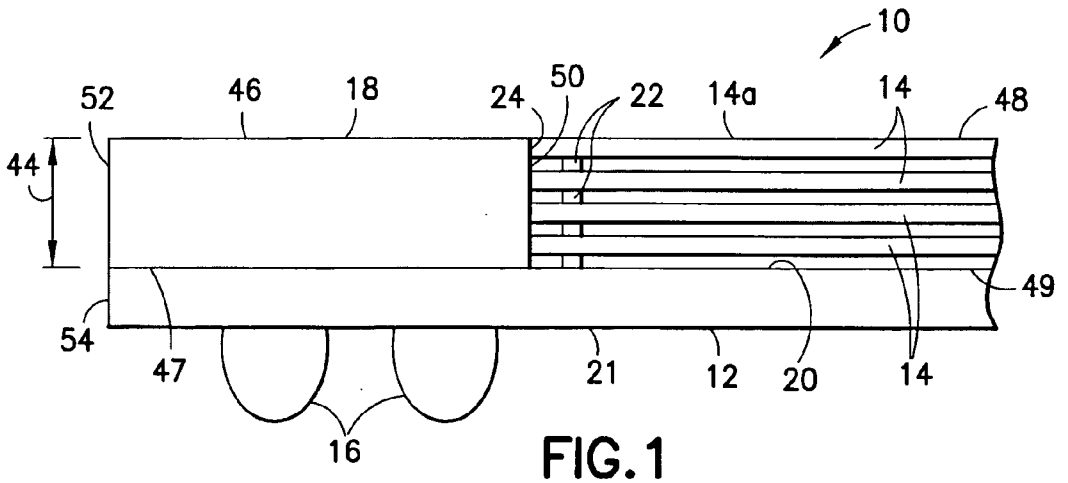

10
52
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14a
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FIG. 1

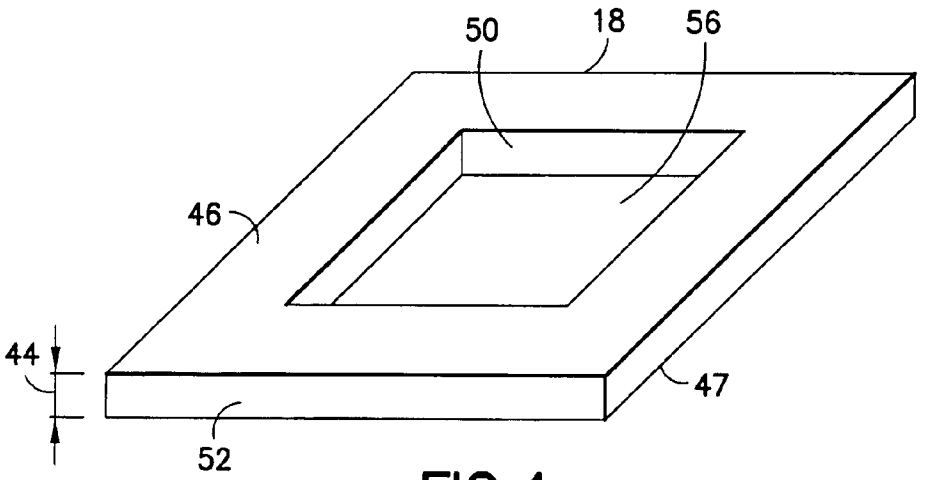

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44
47
52

FIG. 4

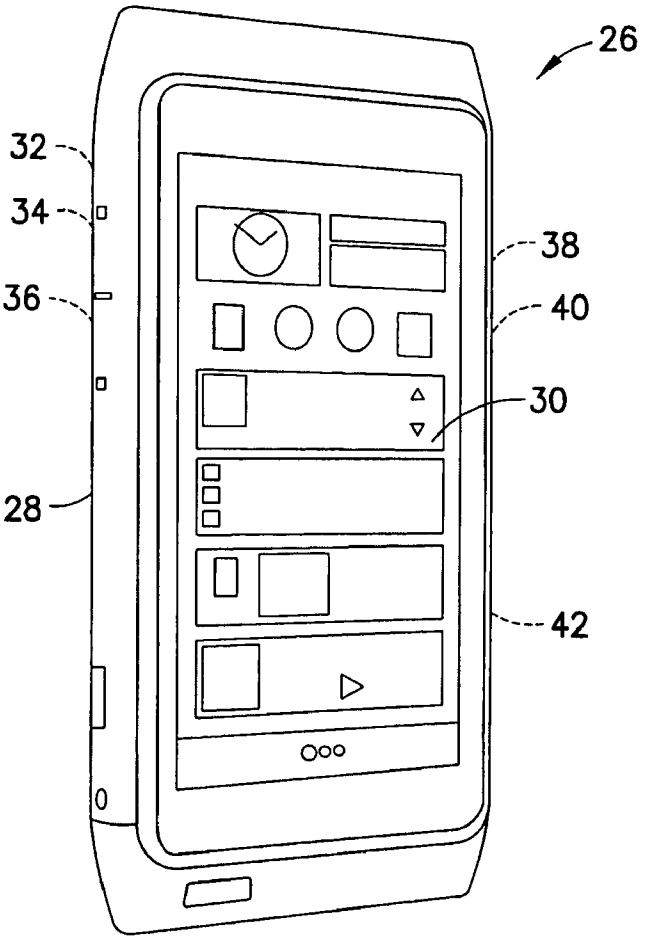


FIG.2

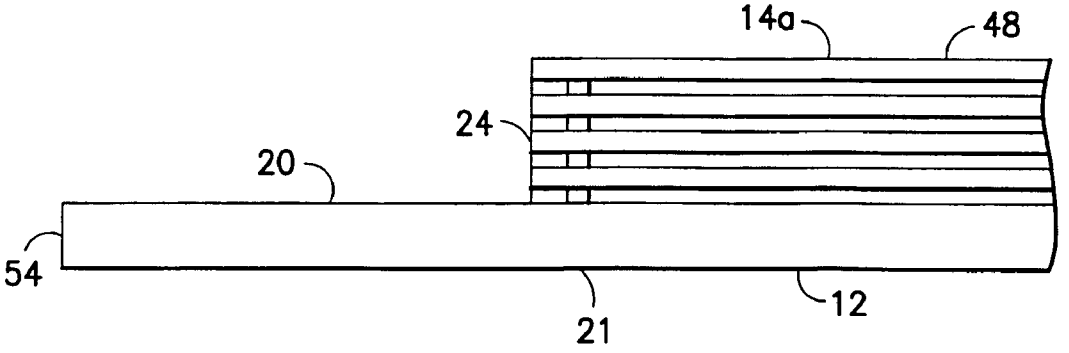


FIG.3

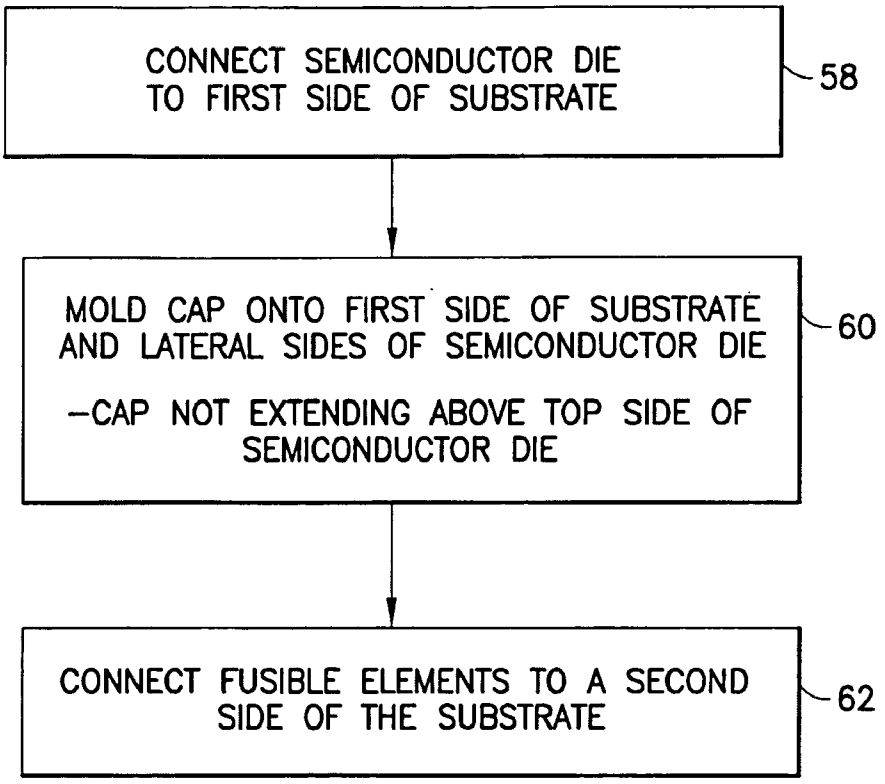

CONNECT SEMICONDUCTOR DIE TO FIRST SIDE OF SUBSTRATE
58
MOLD CAP ONTO FIRST SIDE OF SUBSTRATE AND LATERAL SIDES OF SEMICONDUCTOR DIE
–CAP NOT EXTENDING ABOVE TOP SIDE OF SEMICONDUCTOR DIE
60
CONNECT FUSIBLE ELEMENTS TO A SECOND SIDE OF THE SUBSTRATE
62

FIG.5

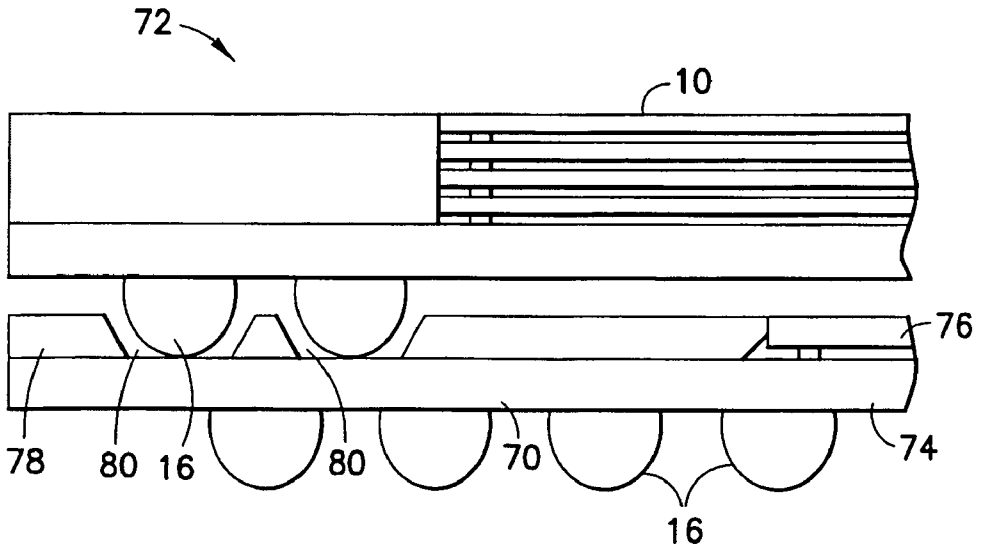

72
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78
80
16
80
70
74
16

FIG.6

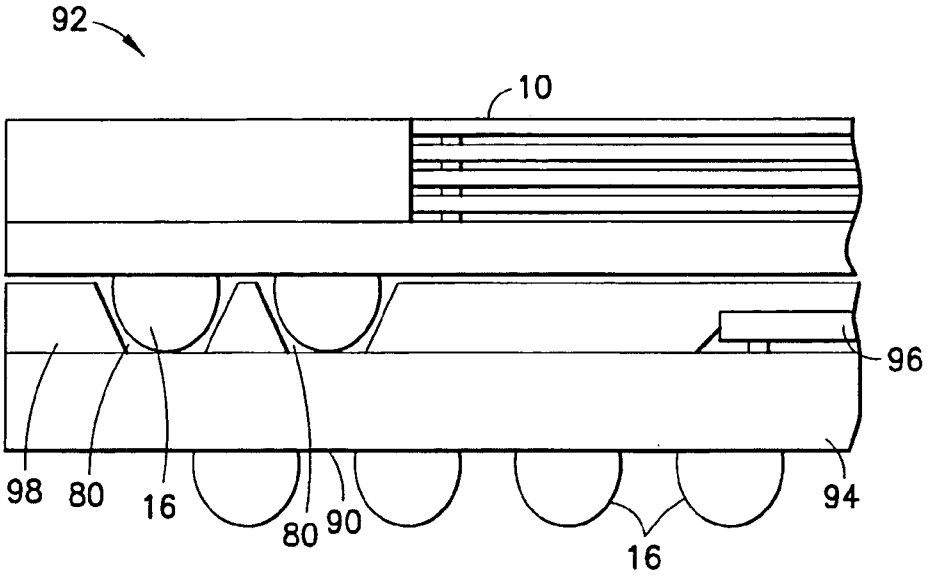


FIG.7

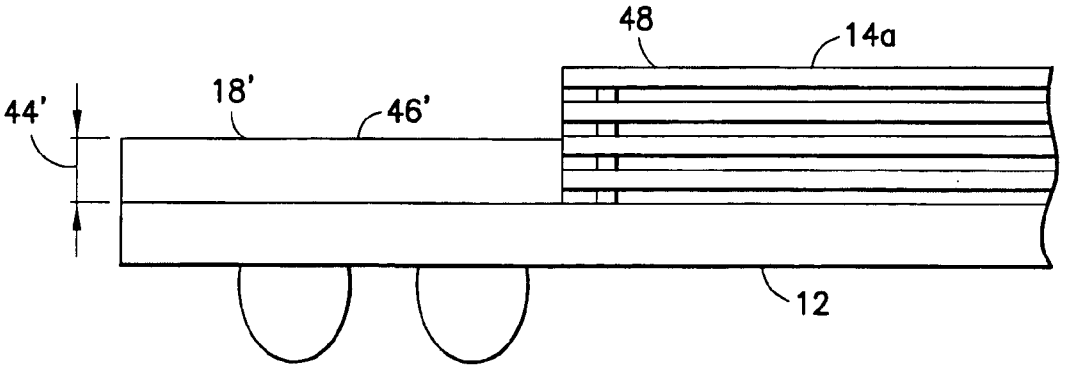


FIG.8

DEVICE WITH MOLD CAP AND METHOD THEREOF

BACKGROUND OF THE INVENTION

[0001] 1. Field of the Invention

[0002] The invention relates to a semiconductor device and, more particularly, to a device having a mold cap around a silicon die.

[0003] 2. Background

[0004] A die in the context of integrated circuits is a small block of semiconducting material, on which a given functional circuit is fabricated. In electronic engineering, a through-silicon via (TSV) is a vertical electrical connection (via) passing completely through a silicon wafer or die. TSV technology is important in creating 3D packages and 3D integrated circuits.

[0005] A three dimensional integrated circuit (3D IC) is a single integrated circuit built by stacking silicon wafers and/or dies and interconnecting them vertically so that they behave as a single device. By using TSV technology, 3D ICs can pack a great deal of functionality into a small "footprint." In addition, critical electrical paths through the device can be drastically shortened, leading to faster operation.

[0006] A 3D package (System in Package, Chip Stack, Multi-Chip Modules (MCM), etc.) contains two or more chips (integrated circuits) stacked vertically so that they occupy less space. An alternate type of 3D package comprises ICs which are not stacked, but a carrier substrate containing TSVs is used to connect multiple ICs together in a package. In most 3D packages, the stacked chips are wired together along their edges. This edge wiring increases the length and width of the package and usually requires an extra "interposer" layer between the chips. In some new 3D packages, through-silicon vias replace edge wiring by creating, vertical connections through the body of the chips. The resulting package has no added length or width. Because no interposer is required, a TSV 3D package can also be flatter than an edge-wired 3D package. This TSV technique is sometimes also referred to as TSS (Through-Silicon Stacking or Thru-Silicon Stacking).

SUMMARY

[0007] The following summary is merely intended to be exemplary. The summary is not intended to limit the scope of the claimed invention.

[0008] In accordance with one aspect of the invention, a device is provided including a substrate; at least one semiconductor die on a first side of the substrate; and a mold cap molded on portions of the first side of the substrate and on lateral sides of the at least one semiconductor die. The mold cap is not molded onto a top side of the at least one semiconductor die.

[0009] In accordance with another aspect of the invention, a method is provided comprising connecting at least one semiconductor die onto a first side of a substrate; after the at least one semiconductor die has been connected to the first side of the substrate, molding a cap onto portions of both the first side of the substrate and lateral sides of the at least one semiconductor die, the cap not extending above a top side of the at least one semiconductor die.

BRIEF DESCRIPTION OF THE DRAWINGS

[0010] The foregoing aspects and other features of the invention are explained in the following description, taken in connection with the accompanying drawings, wherein:

[0011] FIG. **1** is a schematic partial cross sectional view of an example embodiment of the invention;

[0012] FIG. **2** is a perspective view of an apparatus comprising the device shown in FIG. **1**;

[0013] FIG. **3** is a schematic partial cross sectional view of the device shown in FIG. **1** before the mold cap is overmolded onto the device;

[0014] FIG. **4** is a perspective view of the mold cap shown in FIG. **1**;

[0015] FIG. **5** is a block diagram illustrating features of one example method of the invention;

[0016] FIG. **6** is a schematic partial cross sectional view of a package comprising the device shown in FIG. **1**;

[0017] FIG. **7** is a schematic partial cross sectional view of an alternative package comprising the device shown in FIG. **1**; and

[0018] FIG. **8** is a schematic partial cross sectional view of an alternative embodiment of the device shown in FIG. **1**.

DETAILED DESCRIPTION OF EMBODIMENTS

[0019] Although the invention will be described with reference to the example embodiments shown in the drawings, it should be understood that the invention may be embodied in many alternate forms of embodiments. In addition, any suitable size, shape or type of elements or materials could be used.

[0020] Referring to FIG. **1**, there is shown a schematic partial cross sectional view of a device **10** according to an example embodiment of the invention. The device **10** is an electronic component for use in an electronic apparatus. An example of an electronic apparatus **26** having the device **10** is shown in FIG. **2**. In this example the apparatus **26** is a hand-held portable apparatus comprising various features including a telephone application, Internet browser application, camera application, video recorder application, music player and recorder application, email application, navigation application, gaming application, and/or any other suitable electronic device application. The apparatus **26**, in this example embodiment, comprises a housing **28**, a touch screen **30** which functions as both a display and a user input, a receiver **32**, a transmitter **34**, a rechargeable battery **42**, and a controller **36** which may include at least one processor **38**, at least one memory **40**, and software. The device **10** may be used as, for example, a memory in the apparatus **26** or a application-specific integrated circuit (ASIC) in the apparatus **26**. The apparatus **26** is merely shown as an example of an apparatus in which the device **10** could be used, and this example should not be considered as limiting the invention.

[0021] Referring back to FIG. **1**, the device **10** in this example embodiment comprises a substrate **12**, semiconductor dies **14**, fusible elements **16**, and a mold cap **18**. Additional features or elements could be provided. The substrate **12** comprises a printed wiring board type of substrate which is configured to electrically connect the dies **14** to the fusible elements **16**. The semiconductor dies **14** comprise a plurality of dies stacked together as a 3D integrated circuit (IC) **14***a*. However, in an alternate embodiment the device **10** might comprise only one semiconductor die, or the dies might not be stacked exactly as shown. In this example embodiment the dies **14** are interconnected vertically by conductors **22** (passing completely through the dies) so that they behave as a single device. By using through-silicon via (TSV) technology, the 3D IC **14***a* formed by the dies **14** can pack a great deal of functionality into a small "footprint" or area on the side **20**

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of the substrate **12**. In addition, critical electrical paths **22** through the IC **14***a* can be drastically shortened, leading to faster operation. In an alternate embodiment a connection of the dies **14** other than a TSV connection might be used. In the example embodiment shown the IC **14***a* is flip-chip mounted directly on the first side **20** of the substrate **12**.

[0022] The fusible elements **16** comprise solder balls in this embodiment. However, in alternate embodiments any suitable type of fusible element could be provided. The fusible elements are attached to the second side **21** of the substrate opposite the first side **20**. The fusible elements can be melted and subsequently allowed to cool to mechanically and electrically connect the device **10** to another member (not shown). Alternatively, or additionally, a different type of electrical connection to the other member could be provided, such as a through hole contact or surface contact for example.

[0023] The mold cap **18** comprises molded plastic or polymer material which is overmolded onto the first side **20** of the substrate and onto the lateral sides **24** of the IC **14***a* at the same time. Referring also to FIG. **3** the device is shown before the mold cap **18** is formed. As can be seen, the IC **14***a* is attached to the substrate **12** before the mold cap **18** is formed. The fusible elements **16** could be attached to the substrate **12** before or after the mold cap **18** is formed. FIG. **4** shows the mold cap **18** after the mold cap is formed, but without showing the other components of the device **10** merely for the sake of clarity. The mold cap **18** is not formed separately from the device **10**. Instead, the mold cap **18** must be overmolded onto the first side **20** of the substrate and onto the lateral sides **24** of the IC **14***a*.

[0024] "Overmolding" is a specific type of injection molding; not merely any type of molding. The substrate **12** with the IC **14***a* attached can be positioned into a mold (not shown), material is injected into the mold, and the mold cap **18** is thus overmolded onto the two members **12**, **14***a* inside the mold. When the substrate **12** and IC **14***a* are located in the mold, part of the mold contacts and covers the top side **48** of the IC **14***a* so the mold cap **18** is prevented from forming on the top side **48**. Sides of the mold allow the mold cap **18** to be overmolded all the way up to and even with the lateral sides **54** of the substrate **12**. In alternate embodiments the sides **52** might not be even with the sides **54**, and a molding process other than overmolding could be used. The mold cap **18** might be overmolded onto the IC **14***a*, and then the mold cap **18** and IC **14***a* could be attached to the substrate **12**.

[0025] When the mold cap **18** is overmolded onto the surface **20** and sides **24**, the molded material bonds onto the surfaces **20**, **24** and subsequently hardens such that the mold cap mechanically strengthens the substrate **12** and mechanically strengthens connection of the IC **14***a* with the substrate **12** forming a unitary structure. The inner facing surface **50** (see FIG. **4**) of the mold cap **18** is located only around a side perimeter of the IC **14***a*. The outer lateral or perimeter sides **52** could extend to the outer lateral or perimeter sides **54** of the substrate. Thus, with a square or rectangular shaped substrate and a square or rectangular shaped IC **14***a*, the mold cap **18** may have a general picture frame shape with a channel **56** entirely through the mold cap **18** between its top side **46** and its bottom side **47**. The IC **14***a* is located in that channel **56**; preferably occupy the entire channel **56**.

[0026] In the embodiment shown in FIG. **1** the height **44** of the mold cap **18** is about the same height as the IC **14***a* on the substrate **12**. It is desired to not have the top surface **46** of the mold cap **18** extend above the top surface **48** of the IC **14***a*. FIG. **8** shows an alternate embodiment where the mold cap **18'** has a height **44'** less than the height of the IC **14***a*. Thus, the top surface **46'** is lower than the top side **48** of the IC **14***a*. The height of the mold cap is preferably equal to or less than the height of the IC on the substrate. Thus, none of the material of the mold cap **18** extends above the top side **48** of the IC. No portion of the mold cap **18** is located on the top side **48**. The top side **48** of the IC is the highest portion of the device measured from the substrate **12**. In one type of example embodiment the mold cap **18** does not extend between the IC **14***a* and the substrate. However, with another type of example embodiment Molded Under-Fill (MUF) could be used which can both overmold and may have mold under-filling take place at the same time.

[0027] Referring also to FIG. **5**, in one method of the invention at least one semiconductor die **14** is attached to the substrate **12** as indicated by block **58**. As indicated by block **60**, the mold cap **18** is overmolded onto the first side **20** and at the lateral sides **24** of the die(s) **14**, but not extending above the top side **48** of the top dies of the stack **14***a*. The fusible elements **16** are connected to the substrate's second side **21** as indicated by block **62**. As noted above the fusible elements **16** could be attached after the mold cap **18** is formed, but the die(s) **14** must be attached to the substrate **12** before the mold cap **18** is formed. The resultant device **10** forms a Ball Grid Array (BGA) IC device.

[0028] Ball Grid Array (BGA) IC packaging is widely used for mobile applications. Miniaturization is a main driver for the packaging, and thickness or height reduction is especially important in order to realize thinner mobile phone products. Suppliers have been working hard to make memory and ASIC packages as thin as possible without sacrificing quality and reliability. Reduction of every 10 microns in thickness makes sense to make the package thinner as much as possible. Naturally thickness reduction must be realized without sacrificing device quality and reliability, such as package warpage (which could cause soldering problem) or mechanical strength.

[0029] There are two major mobile applications for BGA IC packaging: Memory and ASIC. In a typical memory BGA package, multiple memory dies are wire-bonded and stacked with each other on an organic substrate with a plastic mold cap for protection. A desire for thickness reduction is naturally more demanding in Package-on-Package (PoP) BGA than in stand-alone BGA. An ASIC die is usually flip-chip attached without a mold cap. This type of bare-die flip-chip package often exhibits large package warpage at elevated temperature during soldering process and could cause yield-loss problem. Use of a thicker substrate is effective to reduce package warpage, but it increases PoP stack-up thickness at the same time; so it is not a preferred way. One example embodiment of the present invention may be used in a Ball Grid Array (BGA) package. The idea can comprise a mold cap only around a die or die stack so that the top surface of the die is exposed. The highest vertical level of the mold cap can be the same as or lower than the top surface of the die or die stack.

[0030] One technical challenge which the invention addresses is to reduce the thickness of a Package-on-Package (PoP) assembly. An example embodiment of the invention may comprise a package structure of a partial mold cap with an exposed flip-chip die. As used herein, "partial mold cap" merely means that the mold cap is not located over the top side of the die. If applied to a TSV-stacked memory, the invention

can decrease package thickness by the amount a mold cap **18** would otherwise extend over the die. If applied to a TSV PoP with silicon substrate it reinforces the mechanical strength of the substrate and improves reliability, without increasing stack-up thickness (height).

[0031] Referring also to FIG. **6**, the device **10** is shown in conjunction with a second device **70** to form a package or assembly **72**. The second device **70** comprises a silicon substrate **74**, a semiconductor die **76**, a mold cap **78** and fusible elements **16**. The die **76** is connected with Through-Silicon Via (TSV) connections to the second substrate **74**. For a single die flip-chip application, a TSV connection might not be provided. Instead, flip-chip solder bumps might be provided on the functional surface of the die (the surface facing the substrate). In this embodiment the mold cap **78** has a top surface which is located at or below the top surface of the die **76**. The mold cap **78** comprises Through-Mold Vias (TMV) **80** which allow access to the contact areas on the top side of the substrate **74** for the fusible elements **16** of the device **10**. By use of a TMV technique, where the vias **80** are formed such as by laser-drilling the vias **80** into the mold cap for example, this can increase the area of the mold cap on the substrate **74**. In the example embodiment shown, with use of a TMV technique the area of the mold cap on the substrate **74** can be extended all the way to the outer edges of the substrate **74**. The thin silicon substrate **74** is fragile and may not have enough mechanical strength by itself (i.e. the silicon substrate could crack in reliability testing such as drop testing and temperature cycling testing). Use of the mold cap **78** on the top surface of the substrate **74** around the die(s) makes the assembly **74/78** less fragile and improves mechanical strength without having to use a thicker silicon substrate to improve mechanical strength; which would otherwise increase PoP stack-up thickness.

[0032] Referring also to FIG. **7**, the device **10** is shown in conjunction with a second device **90** to form a package or assembly **92**. The second device **90** comprises an organic (non-silicon) substrate **94**, a semiconductor die **96**, a mold cap **98** and fusible elements **16**. In this embodiment the mold cap **98** has a top surface which is located above the top surface of the die **96**. The mold cap **98** comprises Through-Mold Vias (TMV) **80** which allow access to the contact areas on the top side of the substrate **94** for the fusible elements **16** of the device **10**. By use of a TMV technique where the vias **80** are formed, such as by laser-drilling the vias **80** into the mold cap for example, the increased area of the mold cap on the substrate **94** can reduce warpage of the substrate.

[0033] With an example embodiment of the invention, the new packaging "TSV-stacked" memory technology may be used where very thin multiple dies with TSV (Through-Silicon Via) are, stacked and interconnected with each other, flip-chip mounted on an organic substrate and then have an overmolded cap formed. Total thickness of the TSV-stacked memory is much thinner than wire-bonded memory for a same die count.

[0034] Thickness reduction is naturally more demanding in PoP (package on package) BGA than in standalone BGA. In the past an ASIC die was usually flip-chip attached without a mold cap. This type of bare-die flip-chip package often exhibits large package warpage at elevated temperature during soldering process and could cause yield-loss problem. Use of a thicker substrate is effective to reduce package warpage, but it increases PoP stack-up thickness at the same time so it's not a preferred way. With the invention, TMV (through-mold via) PoP technology may be used which has a mold cap to compensate for or reduce package warpage. The mold cap may have laser-drilled TMV **80** to interconnect, for example, a memory BGA on top.

[0035] FIG. **6** shows an example embodiment for illustrating thickness reduction of PoP. In this example a TSV PoP bottom package may be provided which uses a very thin silicon substrate with TSV (through silicon via). TSV-stacked memory device **10** may be used as a top package to make overall stack height very small. TSV PoP also has an advantage of small package warpage because both the die **76** and the substrate **74** are made of silicon so mismatch of thermal expansion can be minimized. Bare-die **76** height and mold cap **78** height of the ASIC package do not directly affect total PoP **72** stack height. What affects the PoP **72** stack height is the distance from the summit of the solder ball **16** of the ASIC **70** to the top-side ball pad of the ASIC **70** at **80**. Naturally, however, the bare-die **76** height and the mold cap **78** height should be lower than the height of the solder ball of the memory **10** in order to make the memory-ASIC interconnection possible.

[0036] In PoP ASIC packaging, TSV package is quite effective to make PoP stack-up thickness very thin. The problem of a thin silicon substrate being fragile and not having enough mechanical strength is overcome by use of a mold cap. With an example embodiment of the invention, a mold cap, whose X, Y dimension sizes are about the same as a package (such as about 12×12 mm for example) may surround a die (such as about 10×9 mm for example) similar to a picture frame. This way the package thickness or height becomes only as high as the die and no higher. Thus, compared to an equivalent package where the mold cap covers the top surface of the die, a package comprising the invention is less high because there is no mold cap thickness above the top surface of the die.

[0037] As seen in FIG. **6** the invention may be applied to a PoP TSV package on a bottom side. In this example the device **70** forms the PoP TSV package on the bottom side. The device **70** may have a TMV mold cap **78**, but the top surface of the die **76** may be exposed. This way the mold cap **78** reinforces the mechanical strength of silicon substrate **74** and improves package reliability. From a thickness viewpoint, in this case, the TMV mold cap **78** may be a little bit thicker and cover the die top surface (such as seen in FIG. **7**) without sacrificing PoP stackup thickness. However, organic molding material increases package warpage for this silicon substrate package. Therefore, the thickness of a TMV mold is preferably small as much as possible, as long as it provides enough mechanical reinforcement. For a TSV-stacked memory package, the invention can reduce package thickness by the amount of mold cap thickness would otherwise occupy above a die. For a PoP ASIC package with a TSV silicon substrate, the invention can reinforce the mechanical strength of the silicon substrate and improve mechanical reliability, without sacrificing PoP stack-up thickness.

[0038] With an example embodiment of the invention, a device **10** may be provided comprising a substrate **12**; at least one semiconductor die **14** connected directly on a first side **20** of the substrate; fusible elements **16** on a second side **21** of the substrate; and a mold cap **18** overmolded onto portions of the first side of the substrate and on lateral sides **24** of the at least one semiconductor die, where the mold cap is not molded onto a top side **48** of the at least one semiconductor die. The at least one semiconductor die may comprise a plurality of

semiconductor dies connected in a stack. The semiconductor dies may comprise through-silicon via (TSV) connections. A top end **46** of the mold cap may be below the top side **48** of the at least one semiconductor die. The mold cap may have a general square or rectangular shape. The mold cap may have an inner facing surface **50** located only around a side perimeter of the at least one semiconductor die.

[0039] The device **10** may be provided as a first device in a package **72**, **92** having a second device **70**, **90** wherein the second device comprises a second substrate **74**, **94**; at least one second semiconductor die **76**, **96** on a first side of the second substrate; second fusible elements **16** on a second side of the second substrate; and a second mold cap **78**, **98** on the first side of the second substrate and on lateral sides of the at least one second semiconductor die, where the fusible elements **16** of the first device **10** are connected to the second device **70**, **90** at the first side of the second substrate.

[0040] The fusible elements of the first device may extend through through-mold vias (TMV) in the second mold cap. The second mold cap may not be molded onto a top side of the at least one second semiconductor die. The at least one second semiconductor die **76**, **96** may comprise a plurality of second semiconductor dies connected in a stack. The second semiconductor die(s) **76**, **96** may comprise through-silicon via (TSV) connections. A top end of the second mold cap **78** may be below a top side of the at least one second semiconductor die **76**. A top end of the second mold cap **98** may be above a top side of the at least one second semiconductor die **96**. The second mold cap may have a general square or rectangular shape. The second mold cap may have a top face, a bottom face and an inner facing surface located between the top and bottom faces and located only around a side perimeter of the at least one second semiconductor die. The second substrate **74** may comprise silicon substrate, and the second mold cap **78** may be located over substantially the entire first side of the silicon substrate **74** excluding an area of the silicon substrate having the at least one semiconductor die **76** thereon.

[0041] A method may be provided comprising connecting **58** at least one semiconductor die **14** directly onto a first side **20** of a substrate **12**; after the at least one semiconductor die has been connected to the first side of the substrate, molding **62** a cap onto portions of both the first side **20** of the substrate **12** and lateral sides **24** of the at least one semiconductor die **14**, the cap not extending above a top side **48** of the at least one semiconductor die; and connecting **60** fusible elements **16** to a second side **21** of the substrate. Molding the cap may comprise not molding the cap onto the top side of the at least one semiconductor die. Molding the cap may form the cap with a general square or rectangular shape. The method may further comprise subsequently connecting the fusible elements to a second substrate through through-mold vias (TMV) in a second mold cap **78**, **98** on the second substrate **74**, **94**, where the second mold cap is located around at least one second semiconductor die **76**, **96** on the second substrate.

[0042] It should be understood that the foregoing description is only illustrative of the invention. Various alternatives and modifications can be devised by those skilled in the art without departing from the invention. For example, features recited in the various dependent claims could be combined with each other in any suitable combination(s). In addition, features from different embodiments described above could be selectively combined into a new embodiment. Accordingly, the invention is intended to embrace all such alternatives, modifications and variances which fall within the scope of the appended claims.

1. A device comprising:
a substrate;
at least one semiconductor die on a first side of the substrate; and
a mold cap molded on portions of the first side of the substrate and on lateral sides of the at least one semiconductor die, where the mold cap is not molded onto a top side of the at least one semiconductor die.

2. A device as in claim **1** where the at least one semiconductor die comprises a plurality of semiconductor dies connected in a stack.

3. A device as in claim **2** where the semiconductor dies comprise through-silicon via (TSV) connections.

4. A device as in claim **1** where a top end of the mold cap is below the top side of the at least one semiconductor die.

5. A device as in claim where the mold cap has a general square or rectangular shape.

6. A device as in claim **1** where the mold cap has an inner facing surface located only around a side perimeter of the at least one semiconductor die.

7. A package comprising:
a first device comprising the device as in any one of the preceding claims; and
a second device comprising:
a second substrate;
at least one second semiconductor die on a first side of the second substrate; and
a second mold cap on the first side of the second substrate and on lateral sides of the at least one second semiconductor die,
where fusible elements of the first device are connected to the second device at the first side of the second substrate.

8. A package as in claim **7** where the fusible elements of the first device extend through through-mold vias (TMV) in the second mold cap.

9. A package as in claim **7** where the second mold cap is not molded onto a top side of the at least one second semiconductor die.

10. A package as in claim **7** where the at least one second semiconductor die comprises a plurality of second semiconductor dies connected in a stack.

11. A package as in claim **10** where the second semiconductor dies comprise through-silicon via (TSV) connections.

12. A package as in claim **7** where a top end of the second mold cap is below a top side of the at least one second semiconductor die.

13. A package as in claim **7** where a top end of the second mold cap is above a top side of the at least one second semiconductor die.

14. A package as in claim **7** where the second mold cap has a general square or rectangular shape.

15. A package as in claim **7** where the second mold cap has a top face, a bottom face and an inner facing surface located between the top and bottom faces and located only around a side perimeter of the at least one second semiconductor die.

16. A package as in claim **7** where the second substrate comprises silicon substrate, and the second mold cap is located over substantially the entire first side of the silicon substrate excluding an area of the silicon substrate having the at least one semiconductor die thereon.

17. A method comprising:

connecting at least one semiconductor die onto a first side of a substrate; and

after the at least one semiconductor die has been connected to the first side of the substrate, molding a cap onto portions of both the first side of the substrate and lateral sides of the at least one semiconductor die, the cap not extending above a top side of the at least one semiconductor die.

18. A method as in claim **17** where molding the cap does not mold the cap onto the top side of the at least one semiconductor die.

19. A method as in claim **17** where molding the cap forms the cap with a general square or rectangular shape.

20. A method as in claim **17** further comprising connecting fusible elements to a second side of the substrate and subsequently connecting the fusible elements to a second substrate through through-mold vias (TMV) in a second mold cap on the second substrate, where the second mold cap is located around at least one second semiconductor die on the second substrate.

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